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PTO/SB/08b (08-03)

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Substitute for form 1449B/PTO

Sheet

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Complete If Known					
Application Number	10/708,281				
Filing Date	2/22/2004				
First Named Inventor	Roman Chistyakov				
Art Unit	2821				
Examiner Name	Don Kitsun Wong A. / 1 e				
	ZON-016				

_	NON PATENT LITERATURE DOCUMENTS						
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²				
AL	C39	VLADIMIROV, V., Voltage-Current Characteristics Of A Gas Magnetron In the Case Of Intense Cathode Sputtering, Sov. J. Plasma Phys., Jan-Feb. 1981, Pgs. 114-118, Vol. 7, No. 1.					
AL	C40	LUTSENKO, E.I., Instability Mechanisms In A High-Current Straight Discharge At A Low Gas Pressure, Sov. J. Plasma Phys., JanFeb. 1984, Pgs. 87-95, Vol. 10, No. 1.					
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Examiner Signature	K	Date Considered	05-06-2005

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

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PTO/SB/08b (08-03)

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Art Unit	2821				
Examiner Name	Don Kitsun Wong A. Le				
Attomey Docket Number					

NON PATENT LITERATURE DOCUMENTS							
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AL	C38	CHISTYAKOV, Roman, Plasma Source With Segmented Magnetron Cathode, Application No. 10/710,946, Filed: August 13, 2004.					
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Examiner Signature	C.	 Date Considered	05-06-2005

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ELECTRONIC INFORMATION DISCLOSURE STATEMENT

* TRANSPIECTRONIC Version v18 Stylesheet Version v18.0

> Title of Invention

METHODS AND APPARATUS FOR GENERATING HIGH-DENSITY PLASMAS WITH IONIZATIONAL INSTABILITIES

Application Number:

10/708281

Confirmation Number:

2280

First Named Applicant:

Roman Chistyakov

Attorney Docket Number: ZON-016

Search string:

(5015493 or 6124675 or 6222321 or 6296742 or 6327163 or 6342132 or 6355992 or 6359424

or 6413382 or 6633017).pn.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
PL)	1.	5015493	1991-05-14	Gruen		427	38
AL	2	6124675	2000-09-26	Bertrand, et al.		315	111.91
AL	3	6222321	2001-04-24	Scholl, et al.	B1	315	111.21
AL	4	6296742	2001-10-02	Kouznetsov	B1	204	192.12
AL	5	6327163	2001-12-04	Petr	B1	363	124
AL	6	6342132	2002-01-29	Rossnagel	B1	204	192.12
AL	7	6355992	2002-03-12	Via	B1	307	419
AL.	8	6359424	2002-03-19	lida, et al.	B2	323	251
D.	9	6413382	2002-07-02	Wang, et al.	B1	204	192.12
AL	10	6633017	2003-10-14	Drummond, et al.	B1	219	121.57

Signature

Examiner Name	Date
	05-06-2005

APP_ID=10708281

PTO/SB/08a (08-03)

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Substitute for form 1449A/PTO

Sheet

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Application Number	10/708,281					
Filing Date	2/22/2004					
First Named Inventor	Chistyakov					
Art Unit	Not Yet Assigned 2/22/04					
Examiner Name	Not Yet Assigned A. L.					
Attorney Docket Number	ZON-016					

U. S. PATENT DOCUMENTS									
Examiner Initials*	Cite No.1	No.1	No.1	No.1	No.1	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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FOREIGN PATENT DOCUMENTS								
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Initials*	No.1	Country Co	ode ³ Number ⁴ Kind Code ⁵	(if known)	MM-DD-YYYY	MM-DD-YYYY Applicant of Cited Document	Where Relevant Passages or Relevant Figures Appear	sages T ⁶
AL	Bl	wo	98/40532		09/17/1998	Chemfilt R & D		
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Signature	Colonia Coloni	Considered	05 -06 -2003

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. 1 Applicant's unique citation designation number (optional). 2 See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. 3 Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). 4 For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 5 Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. 6 Applicant is to place a check mark here if English language Translation is attached.

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Substitute for	form 1449B/PTO				Complete if Known
				Application Number	10/708,281
INFO	RMATION D	ISCLO	SURE	Filing Date	2/22/2004
STAT	EMENT BY	APPLI	CANT	First Named Inventor	Chistyakov
				Art Unit	Not Yet Assigned 282)
	(Use as many sheets o	as necessary)	i	Examiner Name	Not Yet Assigned A. L. 10)
Sheet	2	of	5		

NON PATENT LITERATURE DOCUMENTS						
Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²			
AL	CI	KOUZNETSOV, et al., A Novel Pulsed Magnetron Sputter Technique Utilizing Very High Target Power Densities, Surface and Coatings Technology, 1999, Pgs. 290-293, Vol. 122, Elsevier.				
AL	C2	STEINBRUCHEL, A Simple Formula For Low-Energy Sputtering Yields, Applied Physics A., 1985, Pgs. 37-42, Vol. 36, Springer, Verlag.				
AL	C3	DAUGHERTY, et al., Attachment-Dominated Electron-Beam-Ionized Discharges, Applied Physics Letters, May 15, 1976, Pgs. 581-583, Vol. 28, No. 10, American Institute of Physics.				
AL	C4	FAJANS, et al., Bifurcations In Elliptical, Asymmetric Non-Neutral Plasmas, Physics of Plasmas, October 2000, Pgs. 3929-3933, Vol. 7, No. 10, American Institute of Physics.				
AL	C5	DEKOVEN, et al., Carbon Thin Film Deposition Using High Power Pulsed Magnetron Sputtering, 46th Annual Technical Conference Proceedings, 2003, Pgs. 158-165, Society of Vacuum Coaters.				
AL	C6	CHOUEIRI, Characterization Of Oscillations In Closed Drift Thrusters, Pgs. 1-19.				
AL	C7	STARK, et al., Electron Heating In Atmospheric Pressure Glow Discharges, Journal of Applied Physics, April 2001, Pg. 3568, Vol. 89, No. 7, American Institute of Physics.				
AL	C8	GUDMUNDSSON, et al., Evolution Of The Electron Energy Distribution And Plasma Parameters In A Pulsed Magnetron Discharge, Applied Physics Letters, May 28, 2001, Pgs. 3427-3429, American Institute of Physics				
AL	C9	TIAN, et al., Experimental Investigation Of The Electrical Characteristics And Initiation Dynamics Of Pulsed High-Voltage Glow Discharge, Journal of Physics D: Applied Physics, Vol. 34, Pgs. 354-359 IOP Publishing Ltd. UK				
AL	C10	MOZGRIN, et al., High-Current Low-Pressure Quasi -Stationary Discharge In A Magnetic Field: Experimental Research, Plasma Physics Reports, 1995, Vol. 21, No. 5, Pgs. 400-409, Interperiodica Publishing				

Examiner Signature	of the second	Date Considered 05-06-2005

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Substitute for fo	orm 1449B/PTO				Complete if Known
				Application Number	10/708,281
INFOR	MATION D	ISCLO:	SURE	Filing Date	2/22/2004
STATE	MENT BY	APPLIC	CANT	First Named Inventor	Chistyakov
				Art Unit	Not Yet Assigned 282/
(t	ise as many sheets	as necessary)		Examiner Name	Not Yet Assigned A.L.
Sheet	3	of	5	Attorney Docket Number	

NON PATENT LITERATURE DOCUMENTS							
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AL	CH	GARRIGUES, et al., Hybrid And Particle-In-Cell Models Of A Stationary Plasma Thruster, Plasma Sources Sci. Technol., 2000, Pgs. 219-226, Vol. 9, IOP Publishing Ltd., UK.					
AL	C12	KUDRYAVTSEV, et al., Ionization Relaxation In A Plasma Produced By A Pulsed Inert-Gas Discharge, Sov. Phys. Tech. Phys., January 1983, Pgs. 30-35, Vol. 28, No. 1, American Institute of	*************				
AL	C13	BIBERMAN, et al., Low-Temperature Plasmas With Nonequilibrium Ionization, Sov. Phys. Usp., June 1979, Pgs. 411-432, Vol. 22, No. 6.					
AL	C14	THORNTON, Magnetron Sputtering: Basic Physics And Application To Cylindrical Magnetrons, J. Vac. Sci. Technol. March/April 1978, Pgs. 171-177, Vol. 15, No. 2.					
AL	C15	HART, et al., Measuring The Growth Of Solitons From Normal Modes, [online]. Nonneutral Plasmas, South Hall Convention Center, November 19, Year unknown.					
AL	C16	HELMERSSON, Metallization By Pulsed High-Power Sputtering, [online]. [retrieved on November 21, 2003]. Retrieved from WWW.inf.liu.se/thinprogram/projects/p2.html.					
AL	C17	PISAREV, Modification Of The Surface Of Perforated Polymer MF-4SK In Low-Pressure, High Current Quasi-Stable Discharge Plasma In Magnetic Field, [online]. [retrieved on December 30, 2003]. Retrieved from WWW.tech-dh-mylstc/dh/ma.nsf/we/0624.					
AL	C18	GUDMUNDSSON, et al., Observation Of Ion-Acoustic Solitons In A Pulsed Magnetron Sputtering Discharge, 56th-Gaseous Electronics Conference-2003, October 24, 2003, Pgs. 1-14.	- 244 44444 4444				
AL	C19	MATOSSIAN, et al., Operating Characteristics Of A 100kV, 100kW Plasma Ion Implantation Facility, Surface Coatings & Technology, 1996, Pgs. 92-97, Vol. 85.	•••••••••••				
AL	C20	FAJANS, et al., Second Harmonic Autoresonant Control Of The l=1 Diocotron Mode In Pure-Electron Plasmas, Physical Review E, September 2000, Pgs. 4131-4136, Vol. 62, No. 3.					

Examiner Signature	Date Considered 05 -06 -2005
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Substitut	e for form 1449B/PTO				Complete if Known
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INF	ORMATION DI	SCLO	SURE	Filing Date	2/22/2004
STA	TEMENT BY	APPLI	CANT	First Named Inventor	Roman Chistyakov
				Art Unit	Not Yet Assigned 282/
	(Use as many sheets as	necessary,		Examiner Name	Not Yet Assigned A . (10)
Sheet	4	of	5	Attorney Docket Number	ZON-016

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AL	C21	J.T. GUDMUNDSSON, et al., Spatial And Temporal Behavior Of The Plasma Parameters In A Pulsed Magnetron Discharge, Surface & Coatings Technology, 2002, Pgs. 249-256, Vol. 161, Elsevier Science					
AL	C22	BIBERMAN, et al., Chapter Eight: Transient Nonequilibrium Plasmas, Kinetics Of Nonequilibrium Low Temperature Plasmas, 1987, Pgs. 321, 360-372, Plenum Publishing Corporation, New York, LISA.					
AL	C23	GUDMUNDSSON, et al., Observation Of Solitons In A Pulsed Magnetron Sputtering Discharge [online]. [retrieved on December 8, 2003]. Retrieved from WWW.ens.org/ans/meet/GEC03/hans/abs/s300.html.					
AL	C24	The State Of The Art In Pulsed High Power [online]. [retrieved on July 15, 2002]. Retrieved from WWW.physiqueindustrie.com/_pulse_power.html.	į				
AL	C25	Encyclopedia Of Low Temperature Plasma, Editor V.E. Fortov, 2000, Volume 3, Pg. 123.	V				
AL	C26	Encyclopedia Of Low Temperature Plasma, Editor V.E. Fortov, 2000, Volume 3, Pg. 119.	~				
AL	C27	CHISTYAKOV, Roman, High Power Pulsed Magnetron Sputtering, Application No: 10/065,277, Filed: September 30, 2002.	(2 100000 00 PAR				
AL	C28	CHISTYAKOV, Roman, Method And Apparatus For Generating High-Density Plasma, Application No: 10/065,629, Filed: November 4, 2002.					
R	C29	CHISTYAKOV, Roman, High Deposition Rate Sputtering, Application No: 10/065,739, Filed: November 14, 2002.					
AL	C30	CHISTYAKOV, Roman, High-Power Pulsed Magnetically Enhanced Plasma Processing, Application No: 10/065,551, Filed: October 29, 2002.					

Examiner Signature	Date Considered	05-06-2005

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				Application Number	10/708,281
INFOR	MATION D	ISCLO	SURE	Filing Date	2/22/2004
STATE	MENT BY	APPLI	CANT	First Named Inventor	Chistyakov
				Art Unit	Not Yet Assigned 272/.
(U	se as many sheets	as necessary))	Examiner Name	Not Yet Assigned A - (19)
Sheet	5	of	5	Attorney Docket Number	

		NON PATENT LITERATURE DOCUMENTS	
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AL	C31	CHISTYAKOV, Roman, High-Density Plasma Source, Application No: 10/249,595, Filed: April 22, 2003.	
AL	C32	CHISTYAKOV, Roman, High-Density Plasma Source Using Excited Atoms, Application No: 10/249,844, Filed: May 122, 2003.	***************************************
AL	C33	CHISTYAKOV, Roman, Generation Of Uniformly Distributed Plasma, Application No: 10/249,773, Filed: May 6, 2003.	··············
AL	C34	CHISTYAKOV, Roman, Plasma Generation Using Multi-Step Ionization, Application No: 10/249,202, Filed: March 21, 2003.	
AL	C35	CHISTYAKOV, Roman, Plasma Source With Segmented Cathode, Application No: 60/481,671, Filed: November 19, 2003.	•
AL	C36	HART, et al., Growth Of Soliton-like Structures From Normal Modes And Particle Loss From A Nonneutral Plasma, [online]. Non-Neutral Plasmas, Archibald/Cochran, 3rd Floor, Tower, November 7, 1995	
AL	C37	HART, et al., Verification Of Solitons Grown From Normal Modes, [online]. Dusty Plasmas And Nonneutral Plasmas I, Imperial Ballroom, Fairmont, November 16, Year unknown.	

Examiner Signature	War and the second seco	Date 05-06-205

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